

Day: Tuesday Date: 8/8/2006 Time: 11:46:10

Inventor Name Search Result

Your Search was:

Last Name = MAEDA First Name = AKIO

Application#	Patent#	Status	Date Filed	Title	Inventor Name
05927620	4268644	150	07/24/1978	VULCANIZABLE RUBBER COMPOSITION	MAEDA, AKIO
06026358	Not Issued	161	04/02/1979	RUBBER COMPOSITION CAPABLE OF GIVING VULCANIZATES HAVING IMPROVED OZONE CRACKING RESISTANCE AND OIL RESISTANCE	MAEDA, AKIO
06158249	4404329	150	06/10/1980	RUBBER COMPOSITION CAPABLE OF GIVING VULCANIZTES HAVING IMPROVED OZONE CRACKING RESISTANCE AND OIL RESISTANCE	MAEDA, AKIO
06162891	4299944	150	06/25/1980	PROCESS FOR PRODUCING EPIHALOHYDRIN COPOLYMER RUBBER	MAEDA, AKIO
06183581	4310643	150	09/02/1980	VULCANIZABLE RUBBER COMPOSITION	MAEDA, AKIO
<u>06591836</u>	Not Issued	166	03/21/1984	SCORCH-INHIBITED ELASTOMERIC COMPOSITION	MAEDA, AKIO
06750995	4569958	150	07/02/1985	SCORCH-INHIBITED ELASTOMERIC COMPOSITION	MAEDA, AKIO
06755586	4694067	150	07/16/1985	RUBBER COMPOSITION FOR DUST COVER BOOTS	MAEDA, AKIO
06838818	4689377	150		RUBBER VULCANIZATE FROM ALKYLENE SULFIDE AND EPIHALOHYDKIN	MAEDA, AKIO
06859142	Not Issued	161	05/02/1986	SIZING AGENT	MAEDA, AKIO
07009983	Not Issued	166	02/02/1987	RUBBER COMPOSITION	MAEDA, AKIO

07152131	4826570	150	02/04/1988	SIZING AGENT	MAEDA, AKIO
07158473	Not Issued	164	02/22/1988	RUBBER COMPOSITION	MAEDA, AKIO
07224277	4952633	150	07/26/1988	RUBBER COMPOSITION	MAEDA, AKIO
07243038	4892731	150	08/09/1988	BIOLOGICAL INTESTINAL ANTISEPTICS	MAEDA, AKIO
07426038	5019630	250	10/24/1989	RUBBERY COPOLYMER, PROCESS FOR PRODUCTION THEREOF, AND VULCANIZABLE ELASTOMER COMPOSITION	MAEDA, AKIO
07985326	Not Issued	161	12/04/1992	PROCESS FOR MAKING FLUORINE-CONTAINING RUBBER LAMINATES AND THE RUBBER LAMINATES PRODUCED THEREBY	MAEDA, AKIO
08339816	5744069	250	11/15/1994	WATER SOLUBLE METAL ANTICORROSIVE	MAEDA, AKIO
08653229	Not Issued	161	05/24/1996	IODO-COMPLEX AND ITS USE	MAEDA, AKIO
10102687	6669537	150	03/22/2002	RESIN DIAMOND BLADE AND OPTICAL WAVEGUIDE MANUFACTURING METHOD USING THE BLADE	MAEDA, AKIO
10294646	Not Issued	71	11/15/2002	Surface treatment method of metal member, and metal goods	MAEDA, AKIO
10699696	Not Issued	80	11/04/2003	Optical waveguide device and manufacturing method therefor	MAEDA, AKIO
10774403	Not Issued	161	02/10/2004	Optical waveguide device and manufacturing method therefor	MAEDA, AKIO
11052786	Not Issued	30	02/09/2005	Optical chip for optical transmission and method of making the same	MAEDA, AKIO
11218592	Not Issued	30	09/06/2005	Method of electroplating	MAEDA, AKIO

Inventor Search Completed: No Records to Display.

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	Туре	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	131023	waveguide\$1 core\$1) near12 (electrooptic\$3 electr\$3 near1 optic\$3 electro\$2 near1 opto\$4 electric\$4	US- PGPUB; USPAT; EPO; JPO; DERWEN T	2006/08/08 11:47
2	BRS	L2	43276	coat\$4) near7 (si silica silicate\$1)	US- PGPUB; USPAT; EPO; JPO; DERWEN	2006/08/08 11:47
3	BRS	L3	260974	silicondiox\$3 silicon adj1 diox\$4) near7 (substr\$4)	154' D/ 1 •	2006/08/08 11:47
4	BRS	L4	8484	L2 same L3	iP. D() •	2006/08/08 11:47
5	BRS	L5	247	L1 and L4	IH: P() •	2006/08/08 11:47

	Type	L #	Hits	Search Text	DBs	Time Stamp
6	BRS	L6	1364	(photoresist\$4 photo near1 resist\$3 photo near4 mask\$3 (laser photo uv) near12 mask\$3) near7 (si silica silicate) near2 (film\$2 coat\$4)	US- PGPUB; USPAT; EPO; JPO; DERWEN	2006/08/08 11:47
7	BRS	L7	24	L5 and L6	IH: D() •	2006/08/08 11:47
8	BRS	L8		etch\$4 near7 (si silica silicate) near2 (film\$2 coat\$4)	IH: D() •	2006/08/08 11:47
9	BRS	L9	7	L7 and L8	IH D() •	2006/08/08 11:47

	Туре	Hits	Search Text
1	BRS	1	10/699696
2	BRS	1	S1 and (ti si)
3	BRS	1	10/699696
4	BRS	1	S3 and (ti si silic\$4)
5	BRS	1	10/699696
6	BRS	1	S5 and (ti si silic\$4 film\$2 substrate\$2 sio\$2 photoresist\$2 groov\$2)
7	BRS	8444	(electrooptic\$4 electro\$4 near1 optic\$4) same (wave near1 guide\$1 waveguide\$1)
8	BRS	9474	(electrooptic\$4 electr\$5 near1 optic\$4) same (wave near1 guide\$1 waveguide\$1)
9	BRS	o	<pre>S11 and (form\$4 near7 waveguide\$1 near7 (insid\$2 within)) near5 (substrat\$2)</pre>
10	BRS	0	<pre>S11 and (form\$4 near7 waveguide\$1 near7 (insid\$2 within)) near5 (wafer substrat\$2)</pre>
11	BRS	О	S11 and (waveguide\$1 near7 (insid\$2 within)) near5 (wafer\$1 substrat\$2)
12	BRS	7922	<pre>(wafer\$1 substrate\$1) near7 (wave near1 guide\$1 waveguide\$1) same (electric\$4 electrod\$2 volt\$4 electr\$5 near1 optic\$3)</pre>
13	BRS	12010	<pre>(wafer\$1 substrate\$1) near7 (wave near1 guide\$1 waveguide\$1 core\$1) same (electric\$4 electrod\$2 volt\$4 electr\$5 near1 optic\$3)</pre>
14	BRS	42840	(sio\$2 glass buffer) near2 layer\$1 near7 (substrat\$3 wafer clad\$4)
15	BRS	39690	(sio\$2 glass buffer) near2 layer\$1 near7 (substrat\$3 wafer)
16	BRS	4239	(sio\$2 glass) near2 layer\$1 near7 (si silica)
17	BRS	17680	(substrat\$2 wafer) near2 (film coat\$4 layer\$1) near7 (si silica)
18	BRS	9866	(sio\$2 glass) near2 (film coat\$4 layer\$1) near7 (si silica)

	DBs		Time	Stamp
1	US-PGPUB; USPAT; E JPO; DERWENT			
2	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/0	06 11:31
3	US-PGPUB; USPAT; E JPO; DERWENT			
4	US-PGPUB; USPAT; E JPO: DERWENT	PO;	2005/12/2	21 17:16
5	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	21 17:17
6	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	22 11:45
7	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	22 13:28
8	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	22 12:12
9	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	22 12:09
10	US-PGPUB; USPAT; E JPO; DERWENT			
11	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	22 12:10
12	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	22 12:13
13	US-PGPUB; USPAT; E JPO; DERWENT			
14	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	22 12:17
15	US-PGPUB; USPAT; E JPO; DERWENT		2005/12/2	
16	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	22 12:21
17	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	22 12:22
18	US-PGPUB; USPAT; E JPO; DERWENT	PO;	2005/12/2	22 12:21

	Type	Hits	Search Text
19	BRS	10298	(sio\$2 glass) near2 (film\$2 coat\$4 layer\$1) near7 (si silica)
20	BRS	10293	(sio\$2 glass) near2 (film\$1 coat\$4 layer\$1) near7 (si silica)
21	BRS	18333	(substrat\$2 wafer) near2 (film\$1 coat\$4 layer\$1) near7 (si silica)
22	BRS	1419	S23 same S24
23	BRS	4204	<pre>(photoresist\$4 ((laser photo uv) same mask\$3)) same (si silica) near2 (film\$2 coat\$4 layer\$1)</pre>
24	BRS	1771	<pre>(photoresist\$4 ((laser photo uv) near12 mask\$3)) near7 (si silica) near2 (film\$2 coat\$4 layer\$1)</pre>
25	BRS	1353	S26 and S27
26	BRS	1	S16 and S29
27	BRS	57	S25 and S27
28	BRS	82790	<pre>(wafer\$1 substrate\$1) same (wave near1 guide\$1 waveguide\$1 core\$1)</pre>
29	BRS	124561	(wave near1 guide\$1 waveguide\$1 core\$1) near12 (electrooptic\$3 electr\$3 near1 optic\$3 electro\$2 near1 opto\$4 electric\$4 electrod\$2 volt\$4 electr\$5 near1 optic\$3)
30	BRS	11310	(sio\$5 glass silicondiox\$3 silicon adj1 diox\$4) near2 (film\$1 coat\$4 layer\$1) near7 (si silica)
31	BRS	66227	<pre>(sio\$5 glass silicondiox\$3 silicon adj1 diox\$4) near2 (film\$1 coat\$4 layer\$1) near7 (si silic\$4)</pre>
32	BRS	96355	(sio\$5 glass silicondiox\$3 silicon adj1 diox\$4) near4 (film\$1 coat\$4 layer\$1) near7 (si silic\$4)
33	BRS	84	S7 and (sio\$1)
34	BRS	0	S11 and (sio\$1)
35	BRS	1	10/699696
36	BRS	1	S11 and ("'Si0.sub.2'")

	DBs		Time S	Stamp
19	US-PGPUB; USPAT; F JPO; DERWENT			
20	US-PGPUB; USPAT; I JPO; DERWENT			
21	US-PGPUB; USPAT; I JPO; DERWENT			
22	US-PGPUB; USPAT; F JPO; DERWENT	EPO;	2005/12/2	2 12:23
23	US-PGPUB; USPAT; I JPO; DERWENT	EPO;	2005/12/2	2 12:27
24	US-PGPUB; USPAT; I JPO; DERWENT			
25	US-PGPUB; USPAT; F JPO; DERWENT			
26	US-PGPUB; USPAT; E JPO; DERWENT			
27	US-PGPUB; USPAT; P JPO; DERWENT			
28	US-PGPUB; USPAT; E JPO; DERWENT	EPO;	2005/12/2	2 12:36
29	US-PGPUB; USPAT; F JPO; DERWENT	EPO;	2005/12/2	2 12:48
30	US-PGPUB; USPAT; E JPO; DERWENT	EPO;	2005/12/2	2 12:41
31	US-PGPUB; USPAT; E JPO; DERWENT	EPO;	2005/12/2	2 12:42
32	US-PGPUB; USPAT; E JPO; DERWENT			
33	US-PGPUB; USPAT; E JPO; DERWENT			
34	US-PGPUB; USPAT; E JPO; DERWENT	EPO;	2005/12/2	2 12:47
35	US-PGPUB; USPAT; E JPO; DERWENT	EPO;	2005/12/2	2 12:46
36	US-PGPUB; USPAT; E JPO; DERWENT	EPO;	2005/12/2	2 12:47

	Type	Hits	Search Text
37	BRS	124561	<pre>(wave near1 guide\$1 waveguide\$1 core\$1) near12 (electrooptic\$3 electr\$3 near1 optic\$3 electro\$2 near1 opto\$4 electric\$4 electrod\$2 volt\$4 electr\$5 near1 optic\$3)</pre>
38	BRS	27057	<pre>(("'SiO.sub.2'") glass silicondiox\$3 silicon adj1 diox\$4) near4 (film\$1 coat\$4 layer\$1) near7 (si silica silicate\$1)</pre>
39	BRS	73825	<pre>(wafer substrat\$2 clad\$5) near12 (film\$1 coat\$4 layer\$1) near7 (si silica silicate\$1)</pre>
40	BRS	12352	S40 and S41
41	BRS	10367	S40 same S41
42	BRS	68733	<pre>(substrat\$2 clad\$5) near12 (film\$1 coat\$4 layer\$1) near7 (si silica silicate\$1)</pre>
43	BRS	2399	S40 same S24
44	BRS	66312	(substrat\$2) near12 (film\$1 coat\$4 layer\$1) near7 (si silica silicate\$1)
45	BRS	9076	S40 same S46
46	BRS	41532	(substrat\$2) near12 (film\$1 coat\$4) near7 (si silica silicate\$1)
47	BRS	16074	(("'SiO.sub.2'") glass silicondiox\$3 silicon adj1 diox\$4) near4 (film\$1 coat\$4) near7 (si silica silicate\$1)
48	BRS	210382	(("'SiO.sub.2'") glass silicondiox\$3 silicon adj1 diox\$4) near4 (substr\$4)
49	BRS	242164	(("'SiO.sub.2'") glass silicondiox\$3 silicon adj1 diox\$4) near7 (substr\$4)
50	BRS	7975	S48 same S51
51	BRS	224	S39 and S52
52	BRS	1303	(photoresist\$4 photo near1 resist\$3 photo near4 mask\$3 (laser photo uv) near12 mask\$3) near7 (si silica silicate) near2 (film\$2 coat\$4)

	DBs		Time Stamp
37	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 12:48
38	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 12:56
39	US-PGPUB; USPAT; JPO; DERWENT		
40	US-PGPUB; USPAT; JPO; DERWENT		
41	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 12:54
42	US-PGPUB; USPAT; JPO; DERWENT		
43	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 12:55
44	US-PGPUB; USPAT; JPO; DERWENT		
45	US-PGPUB; USPAT; JPO; DERWENT		
46	US-PGPUB; USPAT; JPO; DERWENT		
47	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 13:34
48	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 12:58
49	US-PGPUB; USPAT; JPO; DERWENT		
50	US-PGPUB; USPAT; JPO; DERWENT		
51	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 12:59
52	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 13:31

	Туре	Hits	Search Text
53	BRS	22	S53 and S54
54	BRS	5177	etch\$4 near7 (si silica silicate) near2 (film\$2 coat\$4)
55	BRS	7	S55 and S56
56	BRS	1	S11 and (waveguide\$2 'in the' adj3 (substrate\$2))
57	BRS	8526	(electrooptic\$4 electro\$4 near1 opt\$4) same ((waveguide\$2 'in the' adj3 (substrate\$2)) (waveguide\$1 near5 (within insid\$2) adj3 (substrate\$1)))
58	BRS	1742	(photoresist\$4 photo near1 resist\$3 photo near4 mask\$3 (laser photo uv) near12 mask\$3) near10 (si silica silicate) near2 (film\$2 coat\$4)
59	BRS	7	S49 and S59 and S60
60	BRS	6	S61 not S57

	DBs		Time Stamp
	US-PGPUB; USPAT; JPO; DERWENT		
	US-PGPUB; USPAT; JPO; DERWENT		
	US-PGPUB; USPAT; JPO; DERWENT		
56	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 13:26
57	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 13:29
	US-PGPUB; USPAT; JPO; DERWENT		
	US-PGPUB; USPAT; JPO; DERWENT		
60	US-PGPUB; USPAT; JPO; DERWENT	EPO;	2005/12/22 13:35